

ABSTRACT

The present disclosure provides a reaction chamber of semiconductor processing equipment and semiconductor processing equipment, relating to the technical field of semiconductor manufacturing equipment, and is designed to address the problem of easily damaged sealing rings in existing reaction chamber sealing structures. The reaction chamber of the semiconductor processing equipment includes a process tube, a sealing flange, and a sealing ring. The outer wall of the process tube is provided with an annular protrusion, the surface of the annular protrusion near the opening of the process tube being coplanar with the radial plane where the opening lies; the sealing flange is provided on one side of the annular protrusion near the opening, the sealing ring surrounds the opening and is pressed between the sealing flange and the annular protrusion; the sealing flange and the process tube are relatively fixedly arranged. The present disclosure makes the sealing ring of the reaction chamber sealing structure less susceptible to damage.